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Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
M122-1694SERIAL NO.
Filed Herewith

69/885,393

LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
Richard Holscher et al.FILING DATE
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Unknown 1756

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
ICAD	AA	5,472,829	12/95	Ogawa	—	—	
	AB	5,591,566	01/97	Ogawa	—	—	
	AC	5,641,607	06/97	Ogawa et al.	—	—	
	AD	5,648,202	07/97	Ogawa et al.	—	—	
	AE	5,677,111	10/97	Ogawa	—	—	
	AF	5,670,297	09/97	Ogawa et al.	—	—	
	AG	5,698,352	12/97	Ogawa et al.	—	—	
	AH	5,831,321	03/98	Nagayama	—	—	
	AI	5,034,348	07/91	Hartswick et al.	—	—	
	AJ	6,008,124	12/99	Sekiguchi et al.	—	—	
V	AK	5,340,621	08/94	Matsumoto et al.	—	—	
ICAD	AL	5,600,165	02/97	Tsukamoto et al.	—	—	

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
VAD	AM	0-778496 A2/A3	06/97	EPO	—	—		
ICAD	AN	9-55351	02/97	Japan	—	—		
	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AR	McKenzie, D. et al., "New Technology for PACVD", Surface and Coatings Technology 82 (1996), pp. 326-333.
	AS	Shibata, Noburu, "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating For Solar Cells", Jap. Journ. of Applied Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.
	AT	

EXAMINER

K. Duda

DATE CONSIDERED

8-5-02

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1694		SERIAL NO. <u>09/885,893</u> Filed Herewith	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Richard Holscher et al.			
				FILING DATE Filed Herewith		GROUP Unknown <u>1756</u>	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
(CMT) ↓ (CMT)	AA	5,968,324	10/99	Cheung et al.	—	—	
	AB	5,872,385	02/99	Taft et al.	—	—	
	AC	5,883,011	04/99	Lin et al.	—	—	
	AD	5,960,289	09/99	Tsui et al.	—	—	
	AE	6,020,243	02/00	Wallace et al.			
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM	US 99/20029	08/99	PCT Search Report			
	AN	US 99/20030	08/99	PCT Search Report			
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR						
	AS						
	AT						
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1694		SERIAL NO. <u>09/88573</u> <small>Filed Herewith</small>		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANTS Richard Holscher et al.				
				FILING DATE <small>Filed Herewith</small> <u>6-19-01</u>		GROUP <small>Unknown</small> <u>1756</u>		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
KAD	AA	4,954,867	09/04/90	Hosaka	—	—		
	AB	5,441,797	08/15/95	Hogan et al.	—	—		
	AC	5,472,827	12/05/95	Ogawa et al.	—	—		
	AD	5,674,356	10/07/97	Nagayama	—	—		
	AE	5,710,067	01/20/98	Foote et al.	—	—		
	AF	5,731,242	03/24/98	Parat et al.	—	—		
	AG	5,741,721	04/21/98	Stevens	—	—		
	↓	AH	5,759,755	06/02/98	Park et al.	—	—	
KAD	AI	5,838,052	11/17/98	McTeer	—	—		
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ	JP06067019A		Japan (Abstract)	—	—		
KAD	AK	0 471 185 A2	7/91	EPO	—	—		
KAD	AL	0 588 087 A2	8/93	EPO	—	—		
KAD	AM	0 588 087 A3	8/93	EPO	—	—		
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
KAD	AN	ARTICLE: Bencher, C. et al., "Dielectric antireflective coatings for DUV lithography", Solid State Technology (March 1997).						
		pp. 109-114.						
KAD	AO	ARTICLE: Dammel, R. R. et al., "Dependence of Optical Constants of AZ® BARLi™ Bottom Coating on Back Conditions", SPIE						
		Vol. 3049 (1997), pp. 963-973.						
KAD	AP	TEXT: Heavens, O. S., "Optical Properties of Thin Solid Films", pp. 48-49, <u>December 1991</u> .						
KAD	AQ	TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10, <u>December 1976</u> .						
KAD	AR	TEXT: Wolf, S. et al., "Silicon Processing for the VLSI Era", Vol. 1, pp. 437-441, <u>1986</u> .						
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